Improved photoresist coater

Patent number:

TW520070Y

Publication date:

2003-02-01

Inventor:

SHIU MIN-CHIN (TW)

Applicant:

MACRONIX INT CO LTD (TW)

Classification:

- international:

H01L21/027; H01L21/02; (IPC1-7): H01L21/027

- european:

Application number:

TW20000219521U 19990817

Priority number(s):

TW20000219521U 19990817

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Abstract not available for TW520070Y

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